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Substitute for form 1448A/PTO		Complete if Known			
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Application Number	10/787,510		
		Filing Date	February 26, 2004		
		First Named Inventor	Robert F. Steimle et al.		
		Group Art Unit	2812		
		Examiner Name	Unknown		
Sheet	1	of	1	Attorney Docket Number	SC13130TP

U. S. PATENT DOCUMENTS						
Examiner Initials*	Cite No. ¹	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code* (if known)			
BA	BA	2004/0150024	A1	Mazoyer et al.	08-05-2004	

FOREIGN PATENT DOCUMENTS								
Examiner Initials*	Cite No. '	Foreign Patent Document			Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T*
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OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS				
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T*	
BA	BB	KIM, Dong-Won et al.; "Charge retention characteristics of SiGe quantum dot flash memories"; Conference Digest of 60 th Device Research Conference; 2002; 1 pg abstract & pp151-152; IEEE; USA.		
BA	BC	ZHU, Jane G. et al; "Effects of Ion Beam Mixing on the Formation of SiGe Nanocrystals by Ion Implantation"; Proceedings of the 11 th International Conference of Ion Implantation Technology; June 16-21, 1996; 1 pg abstract & pp 690-693; IEEE; USA.		
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Examiner Signature	<i>BA/Revan</i>	Date Considered	04/15/05
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* Unique citation designation number. * Applicant is to place a check mark here if English Language Translation is attached.